

ABSTRACT OF THE DISCLOSUREUNSATURATED OXYGENATED FLUOROCARBONS FOR SELECTIVE
ANISOTROPIC ETCH APPLICATIONS

A mixture and a method comprising same for etching a dielectric material from a layered substrate are disclosed herein. Specifically, in one embodiment, there is provided a mixture for etching a dielectric material in a layered substrate comprising an
5 unsaturated oxygenated fluorocarbon. The mixture of the present invention may be contacted with a layered substrate comprising a dielectric material under conditions sufficient to at least partially react with and remove at least a portion of the dielectric material. In another embodiment of the present invention, there is provided a method for making an unsaturated oxygenated fluorocarbon.

10

Figure 1